

IN THE SPECIFICATION:

Please amend the specification as follows:

Page 4, please amend paragraph [0013] as follows:

[0013] This and other aspects are addressed according to an embodiment of the present invention in a lithographic apparatus including a radiation system configured to supply a beam of radiation; a support configured to support a patterning device, the patterning device configured to pattern the beam according to a desired pattern; a substrate table configured to hold a substrate; a projection system configured to project the patterned beam onto a target portion of the substrate; and a supply configured to supply to a space in the apparatus a composition including ~~at least one of one or more~~ perhalogenated C₁-C₆ alkanes; and one or more compounds consisting essentially of one or more nitrogen atoms and one or more atoms selected from hydrogen, oxygen and halogen.

Page 5, please amend paragraph [0018] as follows:

[0018] According to a further aspect of the present invention there is provided a device manufacturing method including providing a beam of radiation using a radiation system; using a patterning device to endow the beam with a pattern in its cross-section; projecting the patterned beam of radiation onto a target portion of a layer of radiation-sensitive material at least partially covering a substrate; supplying to a space through which the beam passes a composition including ~~at least one of one or more~~ a perhalogenated C₁-C₆ ~~alkanes~~ alkane and one or more compounds consisting essentially of one or more nitrogen atoms and one or more atoms selected from hydrogen, oxygen and halogen; and producing reactive species of the composition.